





The Perfect Solution for Mass Spectrometry.

Modular Design. Powerful Software. Wide Range of Applications.

### The Perfect Solution for Mass Spectrometry.

The combination of high sensitivity, maximum stability and intelligent operation make the PrismaPlus the perfect solution for mass spectrometry.

Its modular design offers you a variety of application options in industrial and analytical environments, in research & development, in leak detection and semiconductor production, as well as in coating technology.

The PrismaPlus is the ideal solution for applications ranging from quality assurance and residual gas analysis right through to complex, quantitative tasks.

The Quadera<sup>®</sup> software is a further plus. In addition to being especially easy to operate, it also serves as an easy-to-read platform for transferring all measured data.

Together with a wide selection of interfaces, such as digital and analog inputs and outputs or Ethernet, integration into your system is easily achieved.

Our product and service professionals around the world stand ready to provide you with application assistance on the implementation of the PrismaPlus. Long years of customer and application-specific experience make Pfeiffer Vacuum your ideal partner.

The added plus for gas analysis!



Accelerator



Coating



**Research & Development** 



### Advantages at a glance

- Modular design offers optimum adaptability
- Compact size yet high performance
- A variety of interfaces make for simple systems integration
- Networkable through Ethernet
- High measurement speed, stability and resolution
- Interchangeability of analyzers and electronics

- Two filaments mean maximum up-time
- Lowest detectable partial pressure
   1 · 10<sup>-14</sup> mbar
- Connectable Pfeiffer Vacuum total pressure gauge
- Intuitive operation of the Quadera<sup>®</sup> software
- World-class support and worldwide on-site service

## The Perfect Solution for Mass Spectrometry.

#### **Overview of technologies**

#### **Biased ionization chamber**

Biasing the ionization chamber results in an extremely low background signal. The electron-emitting filament is positively biased relative to ground. This design prevents desorption of gas particles from the chamber walls, and thus the generation of an undesired background signal by electron stimulated desorption.



#### **Field-axis technology**

One of the most important factors in the performance of a mass spectrometer is the transmission of the ions from the ion source into the mass filter. With the aid of field-axis technology, the ions are able to cross the peripheral fields of the separating system without any noteworthy interaction. This enables a high level of sensitivity (A/mbar) to be achieved without the need for pre and post filters.



## Quadera<sup>®</sup> - The PrismaPlus<sup>™</sup> software!



The Quadera<sup>®</sup> software is a further plus. With its modular design, it offers an easy-to-read, user-friendly platform for capturing and visualizing measured data and parameter records. Complete measurement procedures can be programmed.

- User-friendly, intuitive operation
- Customer-specific user interface
- Automated measurement routines via the integral VSTA script editor
- Measured data interchange through I/O module
- With stored library: Containing definitions of unknown gases
- Simple definition of measurement recipes
- Mass spectrometer data can be linked with external signals



Clicking on the icons in the selection window launches the measurement task.

#### **Measurement modes**



## PT M0a bcd efg

Standay:     5       CSEM/Faraday     6       CSEM/Faraday     6       CSEM/Faraday     6       CSEM/Faraday     6       Sensitive UHV residual gas analysis, analytical applications and leak detection     6       1-100 amu     1       1-200 amu     2       1-300 amu     2       1-300 amu     2       Creating and analysis, analytical applications and leak detection     7       For high-vacuum residual gas analysis; high sensitivity and good linearity     1       Gas-tight ion source     2       For high-vacuum residual gas analysis; high sensitivity and good linearity     2       For UHV residual gas analysis; high sensitivity and good linearity     3       For UHV residual gas analysis; high sensitivity and good linearity     3       For UHV residual gas analysis; minimum outgassing and desorption rate     4       Open ion source     6       for UHV applications     1       Tungsten:     1       for UHV applications     1       Yttriated indium;     2       Iow Gave C     1       To 200 °C     2       Mith VC module for control and signal interchange via an			а	
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<sup>1)</sup> With open ion source only
 <sup>2)</sup> Ion sources with tungsten filament only
 <sup>3)</sup> Electronics removed
 <sup>4)</sup> See dimensions page 11
 <sup>4)</sup> Open cons 10

<sup>5)</sup> See page 10

## The Perfect Solution for Mass Spectrometry.

### **Technical data**

PrismaPlus	QMG 220 F1	QMG 220 F2	QMG 220 F3	QMG 220 M1	QMG 220 M2	QMG 220 M3
Detector		Faraday (F)			C-SEM/Faraday	(M)
Mass range	1–100 amu	1–200 amu	1–300 amu	1–100 amu	1–200 amu	1–300 amu
Rod system, diameter/length			6 mm / 1	00 mm		
Min. detection limit, Faraday <sup>1)</sup>	1.10 <sup>-12</sup> mbar	2 • 10 <sup>-12</sup> mbar	4 ∙10 <sup>-12</sup> mbar	5 • 10 <sup>-12</sup> mbar	1 ⋅ 10 <sup>-11</sup> mbar	2 •10 <sup>-11</sup> mbar
Min. detection limit, C-SEM <sup>1)</sup>	-	-	-	1 ⋅ 10 <sup>-14</sup> mbar	< 2 · 10 <sup>-14</sup> mbar	< 4 · 10 <sup>-14</sup> mbar
Ar sensitivity, Faraday <sup>1)</sup>	1 ⋅ 10 <sup>-3</sup> A/mbar	6 ⋅10 <sup>-₄</sup> A/mbar	3 ·10⁴ A/mbar	5 ·10⁻⁴ A/mbar	3 ·10⁻⁴ A/mbar	1.5 ·10 <sup>-₄</sup> A/mbar
Ar sensitivity, C-SEM <sup>1)</sup>	-	-	-	200 A/mbar	200 A/mbar	100 A/mbar
Max. operating pressure <sup>2)</sup> , Faraday operation			1.10⁴ mbar			
Max. operating pressure, C-SEM operation	-	-	-	1.10⁵ mbar	1.10⁵ mbar	1.10⁵ mbar
Contribution to adjacent mass (40/41) <sup>1)</sup>	< 10 ppm	< 20 ppm	< 50 ppm	< 10 ppm	< 20 ppm	< 50 ppm
Operating temperature, analyzer				150 °C		
Operating temperature, electronics				0-40 °C		
Bakeout temperature, analyzer <sup>3)</sup>				200 °C / 300 °C		
Connection flange				DN 40 CF-F		
Resolution at 10 % peak height				0.5–2.5 amu		
Measurement speed, analog/bargraph scar	1			20 ms – 60 s/an	nu	
Measurement speed, Stair				2 ms – 60 s/am	u	
Measurement speed, MID				2 ms – 60 s/am	u	
Number of measurement channels in MID				128		
Reproducibility of peak ratio <sup>3)</sup>				± 0.5 %		
Interface				Ethernet		
Input, digital				External protec	tion	
Supply voltage				90-260 V AC, 5	0/60 Hz	
Weight <sup>4)</sup>	2.4 kg	2.4 kg	2.4 kg	3.8 kg	3.8 kg	3.8 kg

<sup>1)</sup> For open ion source
 <sup>2)</sup> With emission current reduced to 0.2 mA: 1 · 10<sup>3</sup> mbar

<sup>3)</sup> Defined by order number <sup>4)</sup> For variant with elektronic and analyzer on one axis (0°)

#### Accessories

I/O module 220	PT M28 699
SP 220 power supply (inclusive mains cable)	PT 160 200
ActiveLine, PKR 251 <sup>5)</sup> , 5 · 10 <sup>.9</sup> – 1,000 mbar	PT R26 002
ActiveLine, PKR 261 <sup>5)</sup> , 5 · 10 <sup>.9</sup> – 1,000 mbar	PT R26 252
ActiveLine, PBR 260 <sup>5/6)</sup> , 5 · 10 <sup>-10</sup> – 1,000 mbar	PT R27 000
ActiveLine, TPR 280 <sup>5)</sup> , 5 · 10 <sup>4</sup> – 1,000 mbar	PT R26 950
Connection cable, ActiveLine gauge–QMG 220, 3 m <sup>5)</sup>	PT 448 250-T
DigiLine, PPT 100 <sup>5)</sup> , 1 · 10 <sup>-4</sup> – 1,000 mbar	PT R33 130
DigiLine, HPT 100 <sup>5)6)</sup> , 5 · 10 <sup>.9</sup> – 1,000 mbar	PT R34 130
DigiLine, MPT 100 <sup>5)</sup> , 5 · 10 <sup>.9</sup> – 1,000 mbar	PT R35 130
Connection cable, DigiLine gauge–QMG 220, 3 m <sup>5)</sup>	PT 348 403-T

<sup>5)</sup> Can be used only in conjunction with I/O module <sup>6)</sup> Additional SP 220 power supply necessary

#### Scope of delivery



### Applications

The PrismaPlus is the perfect solution for leak detection, residual gas analysis or complex, quantitative analyses:

- Metallurgy
- Vacuum furnaces
- Accelerators
- Sputter process analysis
- Semiconductor production

- Glass coating
- Research & development
- Vacuum process systems
- Lithography plants



Differential pumped PrismaPlus for processes between  $1\cdot 10^{\,6}$  and 5 mbar



PrismaPlus on a coating system





Dimensions in mm



†**r** ul

6.7



\* Gas-tight ion source = 90.6 Grid ion source = 92



Crossbeam ion source

Dimensions in mm

## QMG 220 M 90°

QMG 220 M 0°

#### A PASSION FOR PERFECTION

Leading. Dependable. Customer Friendly. Pfeiffer Vacuum stands for innovative and custom vacuum solutions worldwide, for German engineering art, competent advice and reliable service.

Ever since the invention of the turbopump, we have been setting standards in our industry and this claim to leadership will continue to drive us in the future.

Are you looking for a perfect vacuum solution? Please contact us:

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